

Form PTO 1449 U.S. DEPARTMENT OF  
COMMERCE  
(Modified) PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO.  
247627US-2SRD DIV

APPLN. SERIAL NO.  
New Div. Appln.

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

YOSHIAKI SAITO, ET AL.

FILED

HEREWITH

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIAT E
TTN	AA	5,659,499	08/19/97	E. Chen, et al.			
	AB	5,956,267	09/21/99	A. T. Hurst, et al.			
	AC	5,940,319	08/17/99	M. Durlam, et al.			
	AD	6,178,074	01/2001	Gill			
	AE	6,233,172	05/2001	Chen et al.			
	AF	5,173,873	12/1992	Wu et al.			
	AG	5,757,056	05/1998	Chui			
	AH	6,054,734	04/2000	Aozana et al.			
	AI	6,205,052	03/2001	Slaughter et al.			
	AJ	6,556,473	04/2003	Saito et al.			
	AK	5,768,181	06/1998	Zhu et al.			
	AL	5,838,608	11/1998	Zhu et al.			
TTN	AM	6,072,718	06/2000	Abraham et al.			
	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
TTN	AO	WO 00/10172	02/24/00	WIPO (with English abstract)		x
TTN	AP	10-4227	01/06/98	Japan		x
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

TTN	AW	J.S. MOODERA, et al., J. Appl. Phys., Vol. 79, No. 8, pps. 4724-4729, "FERROMAGNETIC-INSULATOR-FERROMAGNETIC TUNNELING: SPIN-DEPENDENT TUNNELING AND LARGE MAGNETORESISTANCE IN TRILAYER JUNCTIONS (INVITED)," April 15, 1996
TTN	AX	L.F. SCHELP, et al., Physical Review B, Vol. 56, No. 10, pps. R5747 - R5750, "SPIN-DEPENDENT TUNNELING WITH COULOMB BLOCKADE," September 1, 1997
TTN	AY	Y. SAITO, et al., J. Magnetic. Soc., Vol. 23, No. 4-2, pps. 1269-1272, "SPIN-DEPENDENT TUNNELING THROUGH LAYERED HARD-MAGNETIC NANO-PARTICLES," 1999
TTN	AZ	F. MONTAIGNE, et al., Applied Physics Letters, Vol. 73, No. 19, pps. 2829-2831, "ENHANCED TUNNEL MAGNETORESISTANCE AT HIGH BIAS VOLTAGE IN DOUBLE-BARRIER PLANAR JUNCTIONS," November 9, 1998

Examiner

Date Considered 6/14/04

\*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.